INFORMATION DISCLOSURE CITATION

| Atty. Docket No. | 04329.3100 | Serial No. | Not Yet Assigned |
|------------------|--------------------|------------|------------------|
| Applicants | KeiHAYASAKI et al. | | |
| Filing Date | July 23, 2003 | Group: | Not Yet Assigned |

| | | U.S. PA | TENT DOCUMENTS | 3 | | |
|----------------------|--------------------|---------------|----------------|-------|--------------|----------------------------|
| Examiner Initial* | Document Number | Issue Date | Name | Class | Sub Class | Filing Date If Appropriate |
| | 6,372,413 B2 | 04/16/02 | EMA et al. | | | |
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|--------------|-------------|-------------------|-------------------|--------------------------|
| | | try Class | Sub Class | Translation Yes or No |
| 03/30/01 | JAPAN | | | ABSTRACT |
| 390 01/23/02 | JAPAN | | | ABSTRACT |
| 711 04/20/01 | JAPAN | | | ABSTRACT |
| 7 | 11 04/20/01 | 11 04/20/01 JAPAN | 11 04/20/01 JAPAN | 11 04/20/01 JAPAN |

| OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) |
|---|
| TSURUMUNE, A. et al., "Observation Device, Ultraviolet Microscope and Observation Method", Application No. 10/133,626, filed on April 29, 2002. |
| ITO, S. et al., "Manufacturing System in Electronic Devices", Application No.: 10/092,486, filed on March 8, 2002. |
| TAKAHASHI, R. et al., "Method For Forming a Pattern", Application No. 10/075,619, filed on February 15, 2002. |
| ITO, S. et al., "Pattern Forming Method", Application No.: 10/411,148, filed on April 11, 2003. |
| HAYASAKI, K. et al., "Substrate Treating Method, Substrate-Processing Apparatus, Developing Method, Method Of Manufacturing A Semiconductor Device, And Method Of Cleaning A Developing Solution Nozzle", Application No. 10/351,422, filed on January 27, 2003 |
| |

| Examiner | | Date Considered | | |
|--|--|---|--|--|
| *Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; through citation if not in conformance and not considered. Include copy of this form with communication to applicant. | | | | |
| Form PTO 1449 | | Patent and Trademark Office - U.S. Department of Commerce | | |

Customer No. 22,852

Attorney Docket No.: **04329.3100**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

| In re Application of: |) |
|--|------------------------------------|
| Kei HAYASAKI et al. |) Group Art Unit: Not Yet Assigned |
| Serial No.: Not Yet Assigned |) Examiner: Not Yet Assigned |
| Filed: July 23, 2003 |) |
| For: METHOD FOR FORMING A PATTERN AND SUBSTRATE-PROCESSING APPARATUS |))) |

MAIL STOP PATENT APPLICATION Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. § 1.97(b)

Pursuant to 37 C.F.R. §§1.56 and 1.97(b), applicants bring to the Examiner's attention the documents listed on attached Form PTO-1449. Copies of the listed documents are attached. Applicants respectfully request that the Examiner consider the documents listed on attached Form PTO-1449 and indicate that they were considered by making an appropriate notation on this form. This Information Disclosure Statement is being filed with the above-referenced application.

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Attorney Docket No.: **04329.3100**

The following is listed on the accompanying PTO-1449 and is in a non-English language:

- 1. Japanese Patent Publication No. 2001-085407- discloses a method to correct the critical dimension of a resist pattern. It is corrected by ashing process using ozone irradiated by UV light.
- 2. Japanese Patent Publication No. 2002-023390 discloses a method of slimming a resist pattern. A resist pattern is slimmed by oxygen radical generated from ozone using UV light.
- 3. Japanese Patent Publication No. 2001-110711 discloses a method of removing a resist pattern. A resist pattern is oxidized and removed by super critical water.

Also, an English-language abstract of each document is enclosed.

This submission does not represent that a search has been made or that no better art exists and does not constitute an admission that each or all of the listed documents are material or constitute "prior art." If the Examiner applies any of the documents as prior art against any claim in the application and applicants determine that the cited documents do not constitute "prior art" under United States law, applicants reserve the right to present to the office the relevant facts and law regarding the appropriate status of such documents. Applicants further reserve the right to take appropriate action to establish the patentability of the disclosed invention over the listed documents, should one or more of the documents be applied against the claims of the present application.

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Customer No. 22,852 Attorney Docket No.: 04329.3100

If there is any fee due in connection with the filing of this Statement, please charge the fee to our Deposit Account No. 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW, GARRETT & DUNNER, L.L.P.

Dated: July 23, 2003

Enclosures

RVB/FPD/sci

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